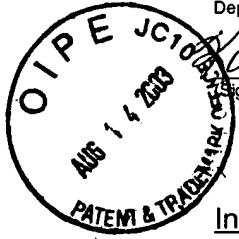


I hereby certify that this correspondence is being deposited with the United States Postal Service as in an envelope addressed to: Commissioner of Patents, P.O. Box 1450, Alexandria, VA 22313, on August 12, 2003. The applicant and/or attorney requests the date of deposit as the filing date.
Depositor: Karen Cing-Mars



Karen Cing-Mars 8/12/03
(signature & date)

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of _____: August 12, 2003
Hendrik F. Hamann et al. : Group Art Unit:
Serial No. 10/604,486 : Examiner:
Filed: 07/25/2003 : International Business Machines Corporation
2070 Route 52
Hopewell Junction, NY 12533

TITLE: SYSTEM AND METHOD OF ALTERING A VERY SMALL SURFACE AREA BY
MULTIPLE CHANNEL PROBE

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, Virginia 22313-1450

Sir:

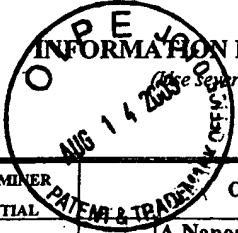
Pursuant to the duty of disclosure set forth in 37 C.F.R. 1.56, and further pursuant to the provisions of 37 C.F.R. 1.97 and 1.98, applicants hereby respectfully submit copies of the prior patents and publications as listed on Form PTO-1449, attached hereto.

In citing these documents, no representation is made nor intended as to the pertinency or non-pertinency of the art, that better art than that listed is not available, or that other art is not applicable.

Respectfully submitted,
Hendrik F. Hamann et al.

BY

Steven Capella
Steven Capella, Attorney
Registration No. 33,086
Telephone No. 845-894-3669

<div style="text-align: center;">  <p>INFORMATION DISCLOSURE CITATION (Use several sheets if necessary)</p> </div>		Docket Number (Optional) FIS9200201 70US1	Application Number 10/604,486
		Applicant(s) Hendrik F. Hamann et al.	
		Filing Date 07/25/2003	Group Art Unit
*EXAMINER INITIAL	OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)		
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EXAMINER		DATE CONSIDERED	
<p>*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</p>			

INFORMATION DISCLOSURE CITATION (Use several sheets if necessary)		Docket Number (Optional) FIS920020170US1	Application Number 10/604,486
		Applicant(s) Hendrik F. Hamann et al.	
		Filing Date 07/25/2003	Group Art Unit
*EXAMINER INITIAL	OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)		
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INFORMATION DISCLOSURE CITATION

(Use several sheets if necessary)

Docket Number (Optional)

FIS9200201.70US1

Application Number

10/604,48'6

Applicant(s)

Hendrik F. Hamann et al.

Filing Date

07/25/2003

Group Art Unit

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